

Serial No.: 10/044,344
Group Art Unit: 2826

AMENDMENTS TO THE CLAIMS

Please amend pending claims 1 and 8 as indicated below. A complete listing of all claims in the application are as follows:

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1. (currently amended) An integrated circuit interconnect comprising:
a wide top metal line;
a wide bottom metal line;
a dielectric layer disposed between the wide top and wide bottom metal lines;
a plurality of vias in the dielectric layer and connecting the wide top and wide bottom metal lines including:
a first via having a width, and
a second via having a width and spaced more than ~~two~~ widths away and less than four widths away from the first via.
2. (original) The integrated circuit as claimed in claim 1 wherein:
the second via is spaced from the first via in a direction perpendicular to the length of the wide top metal line; and including:
a third via having a width and spaced more than two widths and less than four widths from the first via in a direction parallel to the length of the wide top metal line.
3. (original) The integrated circuit as claimed in claim 1 wherein:
the second via is spaced from the first via in a direction parallel to the length of the wide top metal line; and including:
a third via having a width and spaced more than two widths and less than four widths from the first via in a direction perpendicular to the wide top metal line.
4. (original) The integrated circuit as claimed in claim 1 wherein:
the dielectric layer has an opening provided therein equidistant from the first and second vias.
5. (original) The integrated circuit as claimed in claim 4 wherein:
the opening which has a width equal to the width of the first via.

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6. (original) The integrated circuit as claimed in claim 4 wherein:
the opening has a length greater than twice the width thereof.
7. (original) The integrated circuit as claimed in claim 4 wherein:
the opening has a length and the length extends perpendicular to the length of the wide top metal line.
8. (currently amended) An integrated circuit interconnect comprising:
a wide top metal line;
a wide bottom metal line;
a dielectric layer disposed between the wide top and wide bottom metal lines; and
a via-sea in the dielectric layer and connecting the wide top and wide bottom metal lines including:
a first column of vias having a width, and
a second column of vias having a width and spaced more than ~~a two~~ widths away and less than four widths away from the first column of vias.
9. (original) The integrated circuit as claimed in claim 8 wherein:
the second column of vias is spaced from the first column of vias in a direction perpendicular to the length of the wide top metal line; and including:
a first row of vias including a via in the first column of vias having a width and spaced more than two widths and less than four widths from the first column of vias in a direction parallel to the wide top metal line.
10. (original) The integrated circuit as claimed in claim 8 wherein:
the second column of vias is spaced from the first column of vias in a direction parallel to the length of the wide top metal line; and including:
a first row of vias including a via in the first column of vias having a width and spaced more than two widths and less than four widths from the first column of vias in a direction perpendicular to the wide top metal line.
11. (original) The integrated circuit as claimed in claim 8 wherein:
the dielectric layer has an opening provided therein equidistant from the first column of vias and the second column of vias.

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12. (original) The integrated circuit as claimed in claim 11 wherein:
the opening has a width equal to the width of the first column of vias.
13. (original) The integrated circuit as claimed in claim 11 wherein:
the opening has a length greater than twice the width thereof.
14. (original) The integrated circuit as claimed in claim 11 wherein:
the opening has a length and extends perpendicular to the length of the wide top metal
line.